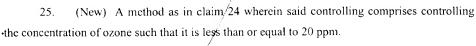
- 15. (New) A method as in claim 9 wherein the surface comprises a low k material.
- 16. (New) A method as in claim 9 wherein the surface comprises a structure selected from a group consisting of a hard disk and a micro electrical mechanical structure.
- 17. (New) A method as in claim 9 wherein said directing comprises directing the aqueous solution at a location proximate a carrier of the surface.
- 18. (New) A method as in claim 17 wherein the location is less than one inch downstream of the surface.
- 19. (New) A method as in claim 9 wherein a pH of the aqueous solution is from about 2 to about 8.
- 20. (New) A method as in claim 9 wherein the aqueous solution comprises reagents selected from a group consisting of carbonate anions, bicarbonate anions, oxalic acid, formic acid, acetic acid, and glycol acids.
- 21. (New) A method as in claim 9, further comprising controlling a temperature of the aqueous solution.
- 22. (New) A method as in claim 21 wherein said controlling comprises lowering the temperature.
- 23. (New) A method as in claim 21 wherein said controlling comprises refrigerating the aqueous solution.
- 24. (New) A/method as in claim 9, further comprising controlling a concentration of ozone in the aqueous solution.





26. (New) A method as in glaim 9 comprising spin etching of the surface.